Study of Annealing Effect on Dilute Nitride Alloys

DISSERTATION

zur Erlangung des akademischen Grades doctor rerum naturalium (Dr. rer. nat.)

> eingereicht zum Fachbereich Physik der Freien Universität Berlin

> > von Jingli Chen

Gutachter:

- 1. Prof. W. D. Brewer, PhD
- 2. Prof. Dr. J. Bosse

eingereicht am: 18.11.2007 Tag der mündlichen Prüfung: 12.12.2007

Abstract

Annealing is an important fabrication process for devices based on the (In)GaAsN group of materials. This thesis studies two topics related to annealing of dilute nitrides:

- 1. The mechanism of structural changes during rapid thermal annealing at different temperatures on a set of GaAsN/GaAs MQWs; the structural and optical properties of the samples were studied by XRD, PL, TEM and Raman Spectroscopy. We found that the main mechanisms for structural change are different in different temperature ranges: at low temperatures ($<750^{\circ}$ C), the principal mechanism is the annihilation of point defects; at medium temperatures ($<750^{\circ}$ C), a short-range ordered structure formed (the negative annealing stage); at high temperatures ($<750^{\circ}$ C), a low density of dislocations is formed by clustering of the residual defects.
- 2. The mechanism of atomic-dimensional structural changes during annealing of different durations of an InGaAsSbN/GaAs SQW was investigated by studying their In K-edge EXAFS spectra. In this study, firstly, the Sb and N atomic fraction ranges in the In first shell were determined. Secondly, a defect-complex-structure related feature was observed in the spectra. We propose that this complex is composed of an N-N dimer and an As-N pair. During annealing of medium duration, part of the defects was annihilated; but when the sample was annealed with a longer duration, a portion of the N-N dimers converted to In-As defects.

Abbreviations

BAC **Band Anticrossing Model** BEEM..... Ballistic Electron Emission Microscopy CB Conduction Band CBE Chemical Beam Epitaxy Disordered Activated Longitudinal-Acoustic (phonons) DALA DFB Distributed Feedback DBR Distributed Bragg Reflector DF Dark Field DLTS Deep-Level Transient Spectroscopy DMH Dimethyl Hydrazine D-W Debye-Waller EXAFS Extended X-ray Absorption Fine Structure FTA Fast Thermal Annealing Full Width at Half Maximum FWHM FT Fourier Transform HRXDR High-Resolution X-Ray Diffraction INGAS InGaAsSbN LD Laser Diode LDA Local Density Approximation LO Longitudinal-Optical (phonons) LT-PL Low-Temperature Photoluminescence LVM Local Vibrational Mode MBE Molecular Beam Epitaxy MOCVD Metal-Organic Chemical Vapor Deposition MQW Multi Quantum Well MSRD Mean Square Relative Displacement PC Photocapacitance PL Photoluminescence PR Photoreflectance Photothermal Reflectance PTR QW Quantum Well RCS Reduced Chi-Square RF Radio Frequency RHEED Reflection High-Energy Electron Diffraction RS Raman Scattering (Spectroscopy) RT Room Temperature RTA Rapid Thermal Annealing

SIMS Secondary Ion Mass Spectrometry

SQWSingle Quantum WellSTASlow Thermal Annealing T_c Critical Temperature T_{tran} Transferring Temperature

TEM Transmission Electron Microscopy

TMGa Trimethyl Gallium

TO Transverse-Optical (phonons)

T-PL Temperature-dependent Photoluminescence

TR-PL Time-Resolved Photoluminescence

UHV Ultra High Vacuum

VCSEL Vertical Cavity Surface Emitting Laser

XRD X-Ray Diffraction

Contents

1	Introduction					
2	Brief Review of Research Works of Dilute Nitrides 2.1 Growth of (In)GaAsN					
3	Review of Works on Semiconductor Annealing 3.1 Investigations of Annealing Effects on (In)GaAsN Materials					
4	Prol	Problems Studied in this Thesis				
5	Ove 5.1 5.2 5.3	rall Properties of GaAsN/GaAs MQWs, As Grown and After Annealing Experimental Setup	31 32 33 33 34 40			
6	Structural Evolution of GaAsN/GaAs MQWs after RTA from Low Temperatures to High Temperatures 6.1 Intensity Change of Photoluminescence after RTA at Different Tempera-					
	6.2	tures	43 44			

		6.2.1	At Low Temperatures ($T < T_c$)	44		
		6.2.2	At Medium Temperatures $(T \approx T_c) \dots \dots \dots \dots$			
		6.2.3	At High Temperatures $(T > T_c)$	47		
7	EXA	FS Stu	dy of RTA Effect on the Atomic Structure of InGaAsSbN Alloy	51		
	7.1	Exten	ded X-ray Absorption Fine Structure (EXAFS)	51		
	7.2		le Growth and Post-Growth Treatment	52		
	7.3	-	imental Setup	53		
	7.4		Analysis	54		
		7.4.1	Background Removal	55		
		7.4.2	Fourier Filtering			
		7.4.3	Goodness of Fit Value			
	7.5	InGa <i>A</i>	AsSbN Sample EXAFS Data Analysis	59		
		7.5.1	Simulation	59		
		7.5.2	Model and Result			
		7.5.3	Possible N-related Complex Structure			
		7.5.4	Change of N-related Complex Structures upon Annealing	64		
		7.5.5	Sb and N Atomic Fractions in the In First-Neighbor Shell	65		
8	Con	clusior	ns	71		
Bi	Bibliography					